

# **Radiation defect chemistry in GaAs and III-V's**

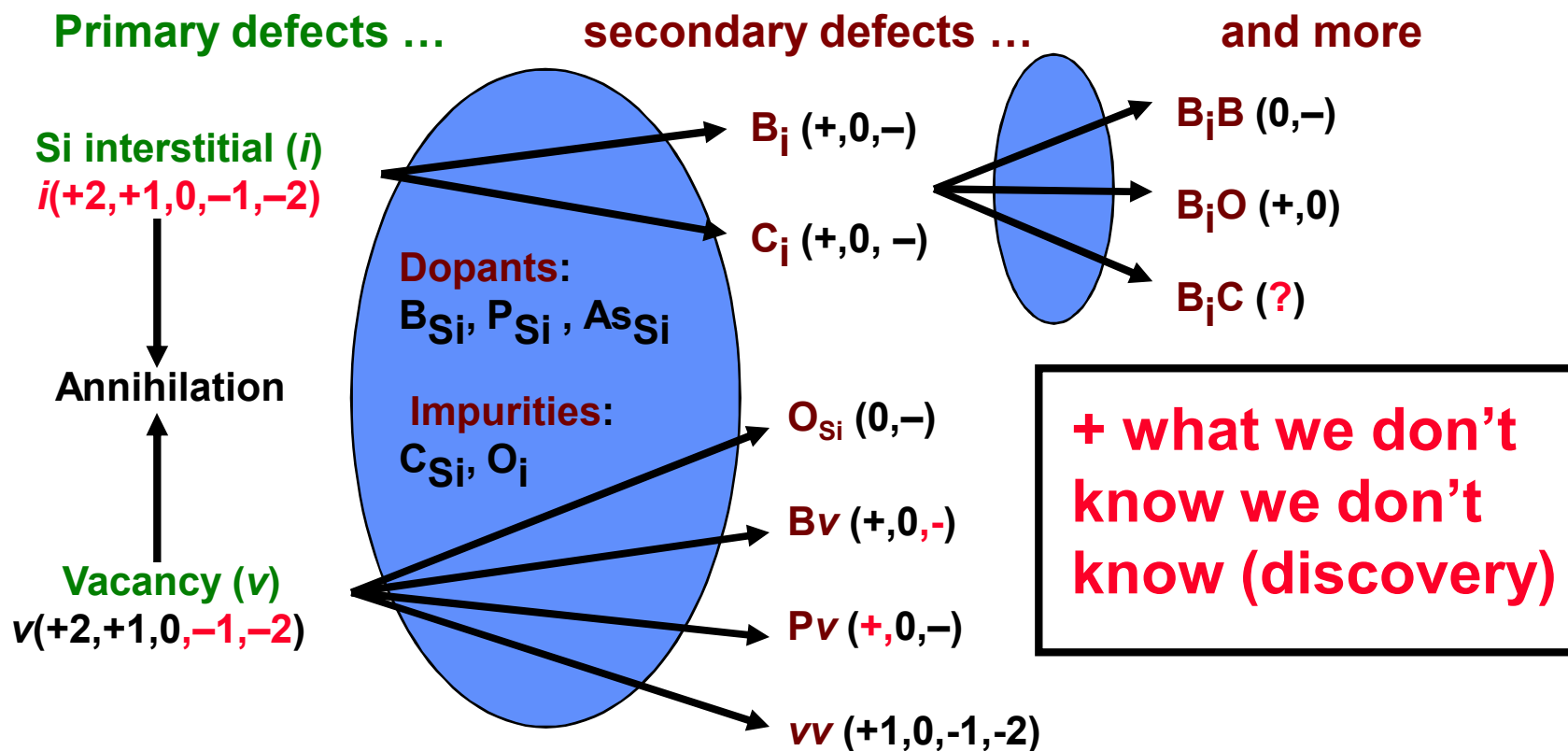
## **Density functional theory (DFT): SeqQuest**

**Thursday, November 18, 2010, 10:00-10:30am**

**Peter A. Schultz**

**Multiscale Dynamic Materials Modeling Dept 1435**

# Radiation defects chemistry: Si



Need to know defects species, levels, chemical evolution ...  
DFT most accurate (sometimes only) probe of defect behavior  
**This chemistry map almost entirely blank in GaAs, III-V's - unknown**

# Requirements for defect levels

- **Experimental uncertainties for defect levels 0.03 eV - 0.1 eV - unknown**
  - Ideally  $kT=0.03$  eV - Si: A-center,  $vv(+/0/1/2-)$ ,  $v(2+/1+/0)$
  - Typically larger, 0.1 eV - Si:  $B_i(-/0)/0.08$  eV,  $B_v$ : a mess ( $U>0.1$  eV), etc
  - Sometimes “infinite” - Si:  $P_v(0/+)$  only recently identified in experiment
  - In GaAs, few levels  $<0.1$  eV, mostly unknown (unknowable?) defects
- **Some numerical evidence from device simulations for 0.1-0.2 eV**
  - Sensitivity Analysis: results not strongly dependent on levels
  - Device simulations already use less accurate data (MD, BCA)
- **Required accuracy: 0.1-0.2 eV (awaiting refined guidance from SA)**
  - Matches accuracy of typical experimental data
  - Improves on existing device simulation practice

Need systematic numerically-driven SA guidance

# DFT challenges

- **Conventional DFT failed for defect levels in semiconductors**
  - (1) “band gap problem” - DFT Kohn-Sham band gaps are awful
  - (2) defect level problem
    - reference level for charge unknown
    - location of band edges of levels (related to band gap problem)
    - e.g.: 10 theory calculations for  $v_{Ga}$  levels = 10 different results
  - (3) unknown (and unassessable) accuracy
    - accuracy of functionals unknown
    - accuracy of pseudopotentials unproven (e.g. 3d: core vs. valence)
  - (4) computational limitations - cell size inadequate to isolate defects
  - (5) lack of good and sufficient data for validation (esp. III-V's)
    - lots of “point solutions” with DFT, but no robust, transferable methods
- **Need to build and justify new approaches, apply to new problems**

**Strategy: incrementally build verified, validated models**

# Incremental development of DFT models

---

## (1) Silicon: lots of good data, with some gaps and unknowns

- develop robust methods for defects (FDSM)
- verify models, validate against comprehensive defect data
  - DFT/SeqQuest with FDSM gives 0.1 eV average, 0.2 eV max error in levels
- predict gaps (interstitials, vacancies), discover unknowns ( $P_V, B_V$ )

## (2) GaAs: more complex system, less good data

- verify models (e.g., PP, cells), learn how to validate with less data
- identify primary radiation defects, predict properties
  - Verified and validated same accuracy as Si, redefined defect assignments
- identify mobile species, and develop and quantify chemical networks

## (3) III-V's: even less good data

- verify models (e.g., PP, cells), adapt validation
- identify primary radiation defects, predict properties
- identify mobile species, and develop and quantify chemical networks

## (4) Alloys, oxides and other materials important in HBT's.

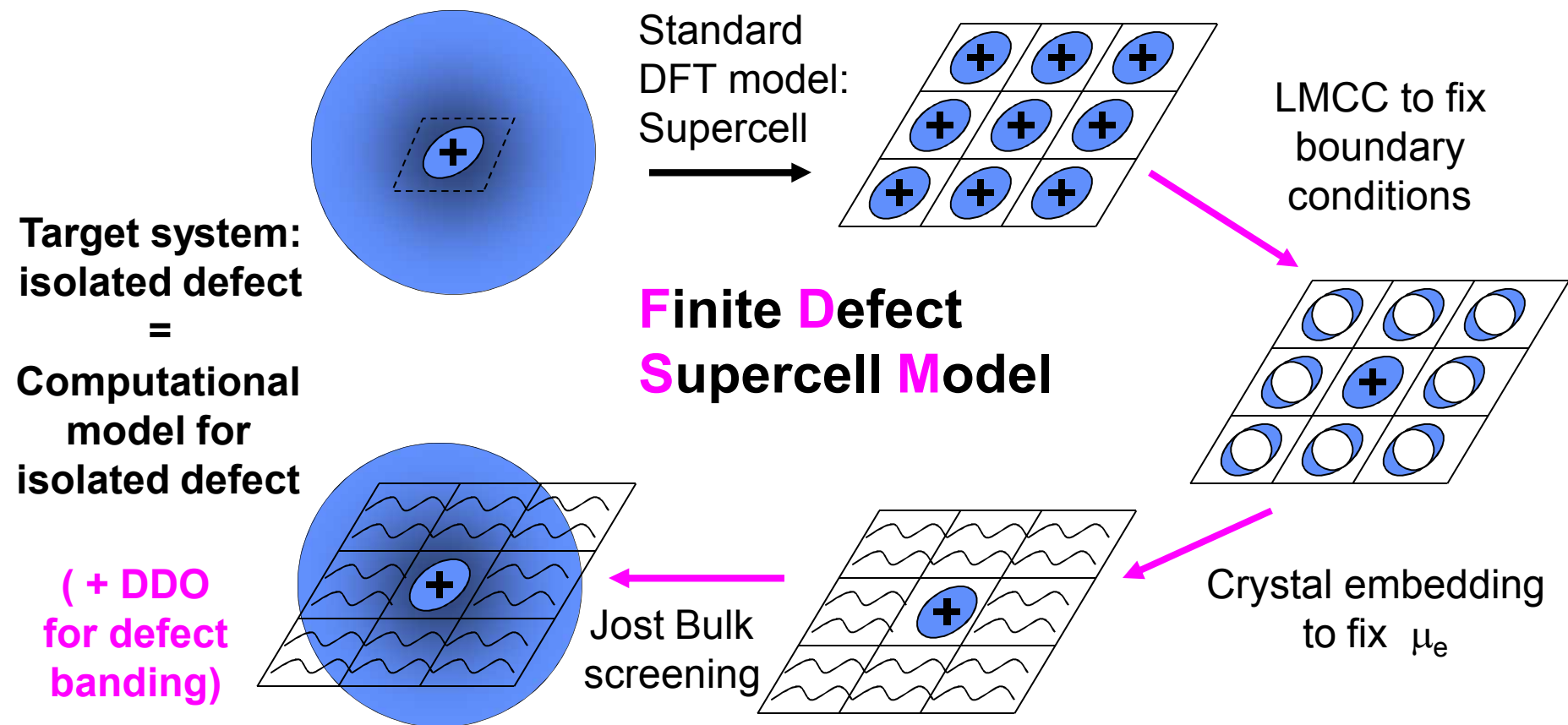
# Computational methods - GaAs and III-V's

- **General purpose DFT code SeqQuest** (<http://dft.sandia.gov/Quest>)
  - Version 2.61j, and development Version dev-2.62/j (equivalent to 2.61j)
  - well-converged (Gaussian-based) local orbital basis
  - both LDA and PBE functionals
  - converged norm-conserving pseudopotentials (Ga,In with both  $Z_{\text{val}}=3,10$ )
  - full force-relaxed ( $<1$  meV total energies)
  - full FDSM ... robust control of boundary conditions
  
- **Large bulk simulation supercells**
  - $a_0=a_0(\text{theory})$  (GaAs:  $5.60\text{\AA}$ (LDA),  $5.63\text{\AA}$ (3d),  $5.74\text{\AA}$ (PBE);  $a_0(\text{expt})=5.65\text{\AA}$ )
  - 216-, 512- and some 64-site (+defect) cubic III-V cells
  - k-sampling: ( $2^3$  for 216- and 512-cells,  $3^2$  for 64-site cell)
  - real-space grids:  $64/96^3$ ,  $216/144^3$ ,  $512/192^3$  ( $96^3$ ,  $144^3$ ,  $192^3$  for GaAs-d0)
  - fully calibrated, verified polarization model
  - all these computational parameters are tested for convergence

Comparable method to Si that yielded 0.1 eV accuracy

# A supercell theory of defect energies

Peter A. Schultz, Phys. Rev. Lett. **96**, 246401 (2006).



**FDSM** - breakthrough for robust calculations of defect levels

# Simple intrinsic defects in GaAs: LDA

P.A. Schultz and O.A. von Lilienfeld, MSMSE **17**, 084007 (2009), 35pp.

216-site results = 512-site

Verification: cell-converged

LDA-3d = LDA to  $\leq 0.1$  eV

Verification: PP converged

Defect band gap =  $\sim 1.54$  eV

Validation: band gap (1.52)

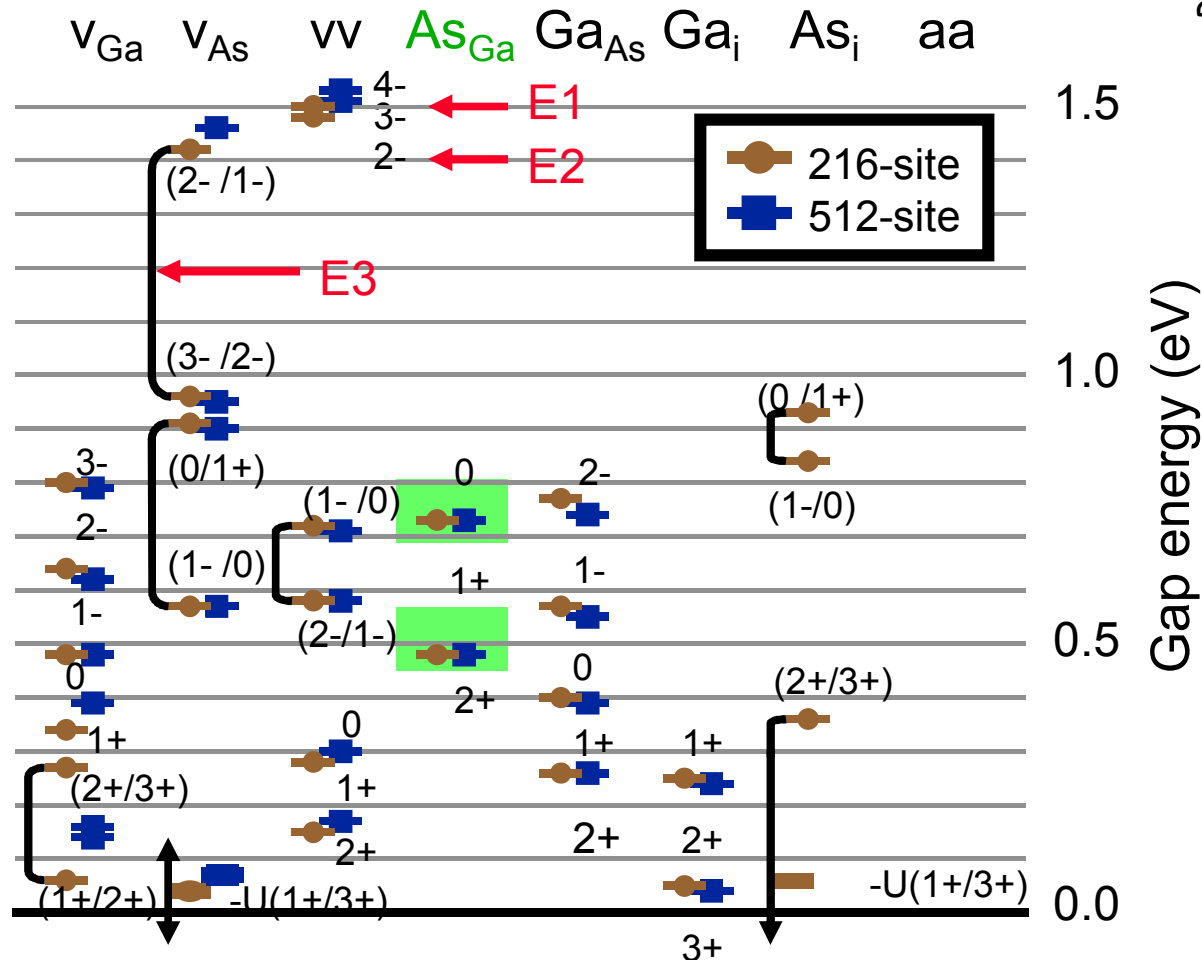
As<sub>Ga</sub> levels = EL2 levels

vGa levels below midgap

Validation: levels  $< 0.1$  eV

DFT/SeqQuest-FDSM

V&V accuracy  $\sim 0.1$  eV



Pure prediction: a GaAs radiation defects Rosetta Stone



# Mobile species: interstitials

## • Unlike in Si, $v$ :GaAs are (both) immobile

- experiment observes these to be stable (until something else annihilates them)
- “simple” nearest-neighbor hops leave trail of high-energy antisites
- second-neighbor hops require strong bond breakings (high-energy)
  - $v_{\text{Ga}}$ : El-Mellouhi & Mousseau, PRB **74**, 205207 (2006)
  - $v_{\text{As}}$ : El-Mellouhi & Mousseau, Appl. Phys. A **86**, 309 (2007)
- while FDSM results contradict levels, they do not contradict lack of mobility

## • $\text{Ga}_i$ is thermally mobile in $p$ -type

- migration barriers, T-H-T:  $\text{Ga}_i[1+]$  1.1 eV,  $\text{Ga}_i[2+]$  0.8 eV,  $\text{Ga}_i[3+]$  0.5 eV,

## • $\text{As}_i$ is thermally mobile in $p$ -type, likely in $n$ -type

- $p$ -type migration barriers, T-H-T:  $\text{As}_i[3+]$ ,  $\text{As}_i[2+]$  <0.5 eV (~validated)
- $n$ -type: flat (<1 eV) structural energy variations in other charge states

## • $\text{As}_i$ is athermally mobile in $p$ -type (~validated), just as in Si

- e.g.,  $\text{T}[3+] + e^- \rightarrow \text{H}[2+] + h^+ \rightarrow \text{T}'[3+] + e^-$
- recombination-enhanced diffusion through bistabilities in other charge states

Transient effects dominated first by  $\text{As}_i$ , second by  $\text{Ga}_i$

# GaAs transient defect chemistry network

Primary defects ...

secondary defects ...

and more

As interstitial  
 $As_i(1-,0,1+,2+,3+)$

Ga interstitial  
 $Ga_i(1+,2+,3+)$

Dopants:  
 $C_{As}, Si_{Ga}$

Antisites,  
Annihilation

Vacancies

$V_{Ga}, V_{As}$

$(3-,2-,1-,0,1+,2+,3+)$

$(v_X, a_X \text{ immobile})$

Reactant initiation ranked by mobility:

$As_i$ : "instant" athermal

$\sim 0.5$  thermal

$Ga_i$ :  $\sim 0.5$  eV thermal in  $p$ -type

Reactant target ranked by concentrations:

$C_{As}$  - in  $p$ -type

$Si_{Ga}$  ( $Si_{As}$ ) - in  $n$ -type

Ignore 2nd order (i-i, clusters) for now

# The dopants - C:GaAs, Si:GaAs

SeqQuest version dev2.62/j, LDA, Ga(Z=3) PP, 216-site cell

	$C_{As}[1-]$	$C_{Ga}[1+]$	$Si_{As}[1-]$	$Si_{Ga}[1+]$
<b>Formation Energy</b> (eV)				
at CB ( <i>n</i> -type)	1.42	4.56	0.34	0.95
at VB ( <i>p</i> -type)	2.96	3.02	1.88	-0.59

## Energy Levels

(eV, cf. CB; n/x=not exist)

E(1-/0)	n/x	-0.28	n/x	n/x
E(0/1+)	n/x	-0.44	n/x	n/x

Carbon exclusively on As site

Si is amphoteric (dopant on Ga site, acceptor on As)

Consistent with experiment (and previous DFT)

Sanity check - not *quantitative* validation

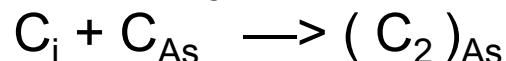
# Defect reactions and energies

Thermodynamic (non-charge conserving)

## As interstitial:

p-type:

(VB edge)



$(\text{C}_2)_{\text{As}}$  is terminus of chemistry

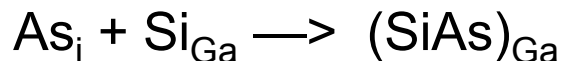
Reaction energy

-1.35 eV

-3.23

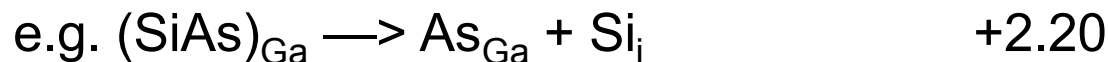
n-type:

(CB edge)



$(\text{SiAs})_{\text{Ga}}$  is terminus of chemistry

but perhaps source of delayed release of  $\text{As}_i$



$(\text{SiAs})_{\text{Ga}}$  is strongly bound vs. dissociation to  $\text{Si}_i$

## Ga interstitial:

n-type:

(CB edge)



$\text{Si}_i$  will be mobile (just as in Si), not a terminus

-0.92

# Defect complex energy levels

(in eV)	$C_i$ (cf VB)	$(C_2)_{As}$ (cf VB)	$Si_i$ (cf CB)	$(SiAs)_{Ga}$ (cf CB)
$E(2-/1-)$	+1.23	n/x	-0.14	-0.33
$E(1-/0)$	+1.04	+1.18	-0.03	+0.71
$E(0/1+)$	+0.53	+0.97	-0.71	-1.03
$E(1+/2+)$	+0.32	n/x	-0.40	-1.35

Complexes have complicated structures, bistabilities

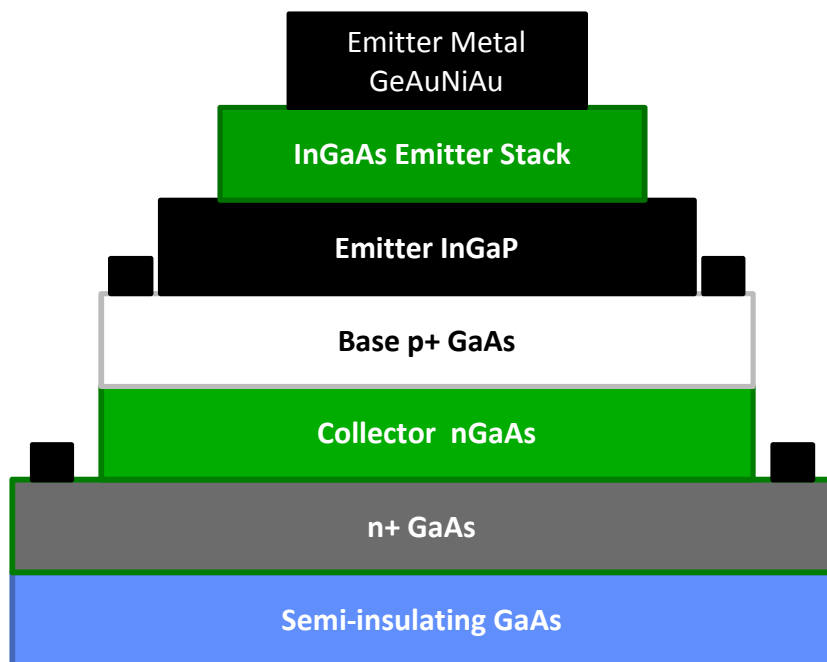
Lead to -U transitions in several places

$(SiAs)_{Ga}[2-]$ ,  $[1-]$  states thermodynamically inaccessible

Levels can be used to extend defect physics package in GaAs

# HBT model need more than GaAs

## HBT stack



AlGaAs and InGaP  
are important in HBT devices

Need defect physics for:  
InP and GaP, AlAs

Then need to extend that  
defect physics to alloys.

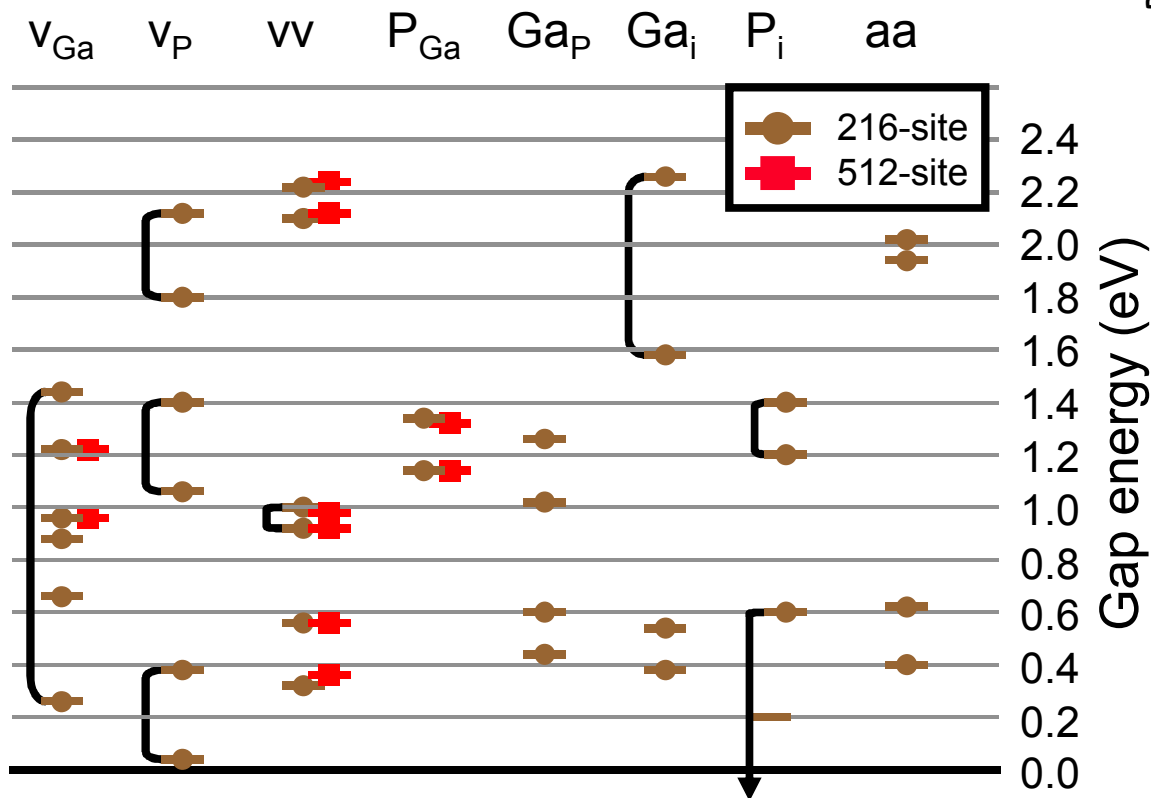
# GaP: Simple intrinsic defects

216-site results = 512-site  
Verification: cell-converged

Defect band gap = ~2.4 eV  
Validation: band gap (2.35)

Mobile species:  
P<sub>i</sub>, thermal (~0.5 eV)  
and athermal p-type  
Ga<sub>i</sub>, migration barriers ~1.0

Similar to GaAs ...  
... with some differences



Pure prediction: defect physics of GaP almost unknown

# InP: Simple intrinsic defects

216-site results = 512-site  
Verification: cell-converged

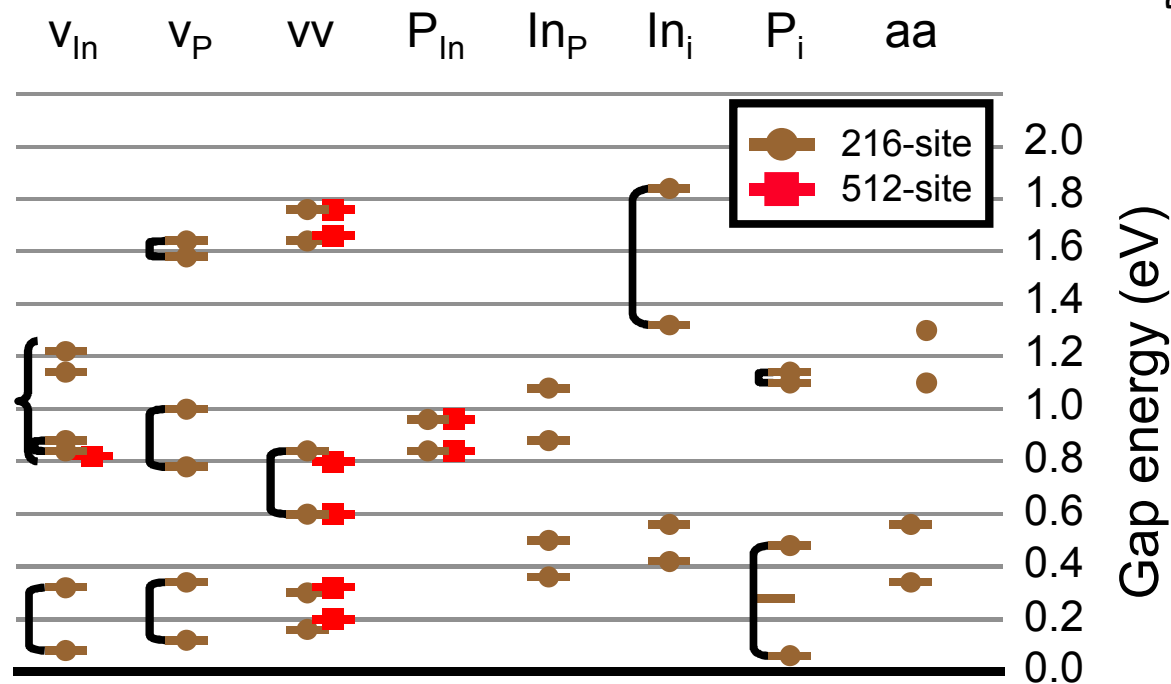
Defect band gap = ~1.7 eV  
Validation: band gap (1.42)

Mobile species:

$P_i$ , thermal (~0.5 eV)

and athermal p-type

$In_i$ , barriers > 0.7 eV



Similar to GaAs, GaP

Some difference, but same mobile species -> similar defect chemistries

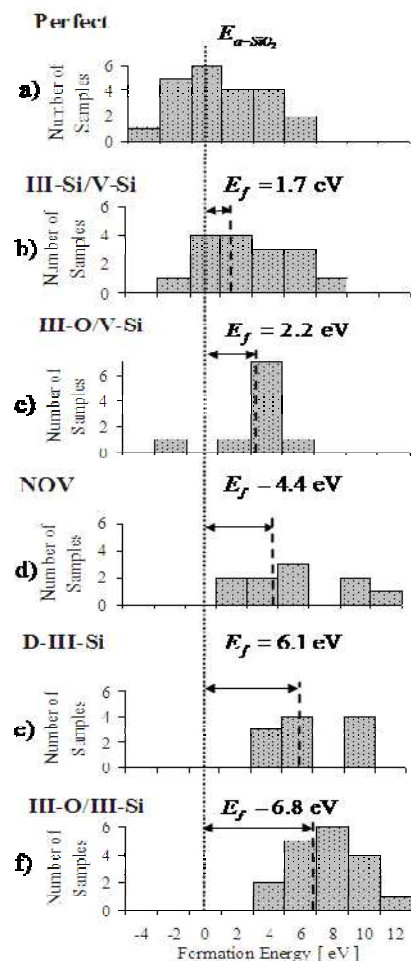
InGaP alloy within reach, intermediate between InP, GaP?



# Enabling progress on oxides

Collaboration with Purdue (ASC/PSAAP program) and PNNL

N. Anderson, R. Vedula, A. Strachan (Purdue), R. Van Ginhoven (PNNL)



## Strategy:

- (1) MD (ReaxFF) to generate **many** hi-fidelity samples both stoichiometric and O-deficient (60 each)
- (2) DFT (SeqQuest/PBE) to screen structures
- (3) identify non-artifact “defects”, compute energies
- (4) model charge states, diffusion and surfaces

Advance: accurate, statistical approach for a-SiO<sub>2</sub>  
Prediction: isolated III-Si (E' centers), without v<sub>O</sub>

Advance: FDSM approach for amorphous systems  
New capability: defect levels (charge traps) in oxides

Progress made outside of QASPR

Methods now enable quantitative studies of oxides

# Path forward

---

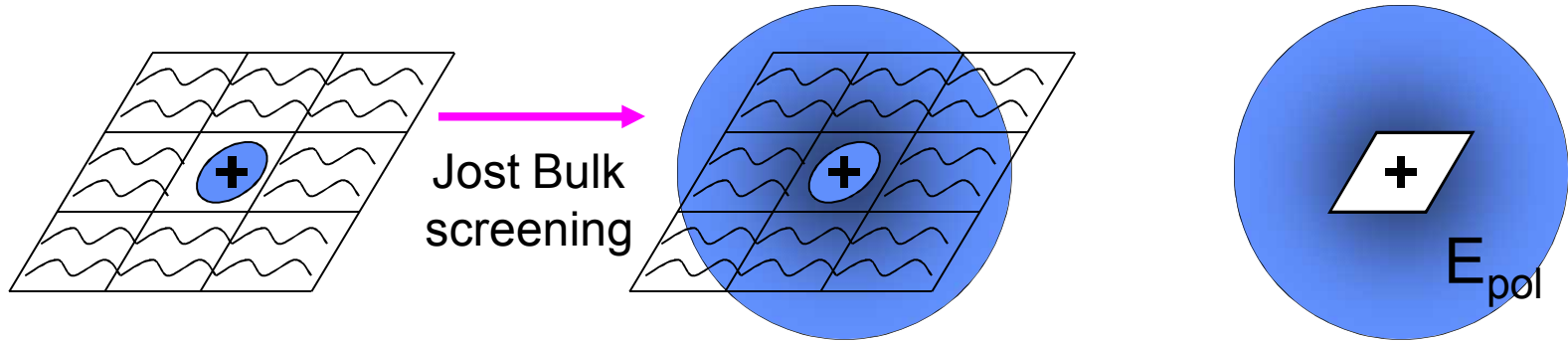
- Impurity-defect chemistry - Si (*n*-type), C (*p*-type)
  - clean up chemical networks, need experiment to filter possibilities
  - submitted to HEART-2011, to be submitted to peer-reviewed journal - March?
- Set up baseline defect physics for other III-V - get ahead of engineering needs
  - write/publish GaP/InP defect physics - Spring?
  - AIAs defects submitted to MRS 2011 Spring Meeting
  - identify mobile species, and begin to scope radiation chemistry networks
  - scope issues for extending to HBT-relevant alloys, e.g. InGaP
- Nurture oxide collaborations: ASC/PSAAP, AFRL, quantum computing
  - SiO<sub>2</sub> bulk and SiO<sub>2</sub>/Si interfaces (PRL submitted, more papers coming)
- Comprehensive VV-UQ plan for DFT for defect physics - Fall 2011?
  - methods now sufficiently developed to enable meaningful plan

DFT has achieved accuracy necessary for engineering needs  
DFT studies can meet engineering timeline constraints

# - extra slides -

---

# The polarization model and verification



For extrapolation to infinite cell, need energy of screening outside of cell.  $E_{pol}$

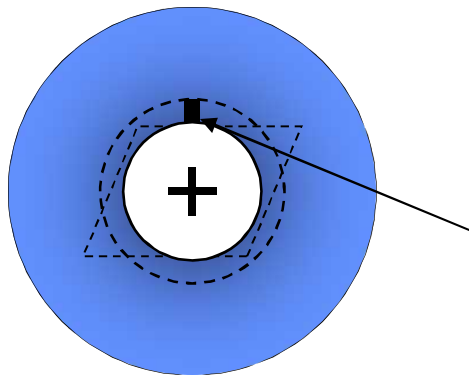
Jost model: 
$$E_{pol} = \frac{(1 - 1/\epsilon_0) q^2}{R_{jost}}$$

$$R_{jost} = R_{vol} - R_{skin}$$

$q$  = charge on defect

$$R_{jost} = R_{vol} - R_{skin}$$

$R_{vol}$  = radius of volume sphere



Two parameters for any material

$R_{skin}$  = unscreened volume **inside** cell.  
fit: =1.5(1) bohr

$\epsilon_0$  = static dielectric constant - expt

Si	GaAs	InP	GaP	AlAs	InAs
11.8	13	12.5	11.2	10.1	15.15

## III-V: The DFT Defect Gap

- Usual band gap definition: CB to VB energy
  - cannot compute directly in DFT (Kohn-Sham (KS) gap is wrong predictor)
- Defect band gap: range of transition energies for local defects

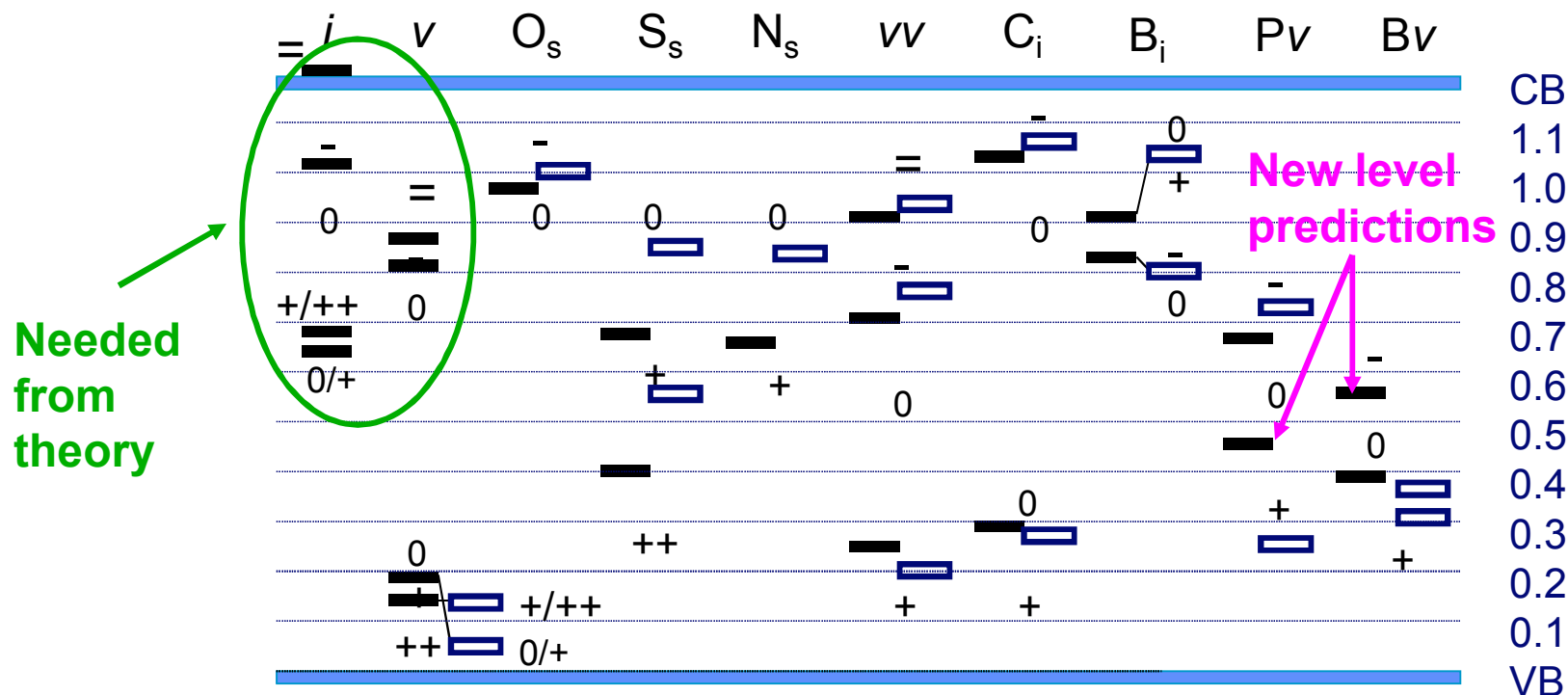
<b>Si</b>			<b>AlAs</b>		
<b>1.17 eV</b>			<b>2.16<sup>i</sup> eV</b>		
	KS	Defect		KS	Def.
lda	0.49	1.2	lda	1.37	2.2
pbe	0.62	1.2	pbe	1.53	n/a

$\epsilon_0 = \epsilon_0(\text{expt})$   
 $R_{\text{skin}} = 1.6(1)$   
**Verified polarization model**

<b>GaAs</b>			<b>GaP</b>			<b>InP</b>		
<b>1.52 eV</b>			<b>2.35 eV</b>			<b>1.42 eV</b>		
	KS	Def.		KS	Def.		KS	Def.
lda	0.83	1.54	lda	1.51	2.3	lda	0.67	1.7
lda-3d	0.47	1.51	lda-3d	1.47	n/a	lda-3d	0.66	1.7
pbe	0.45	1.44	pbe	1.74	n/a	pbe	0.47	n/a
pbe-3d	0.13	n/a	pbe-3d	1.52	n/c	pbe-3d	0.46	n/c

**DFT: defect band gap accurate for interesting III-V**

# Si: DFT/PBE vs. Experimental Levels



... and  $v_2P(=/-/0/+)$ ,  $vP_2(-/0)$ ,  $v_2O(=/-/0+/2+)$ ,  $v_2O_2(=/-/0+/2+)$ ,  $H_i(-/0/+)$  ...  $O_i$ ,  $P_s$ ,  $B_s$ ,  $C_s$ ,

DFT “defect gap” matches experiment.

DFT/PBE max error=0.20 eV, mean |error|=0.10 eV - VALIDATION

Band gap problem not seen in **total-energy-based** defect levels

# Si: new P-v and B-v charge states

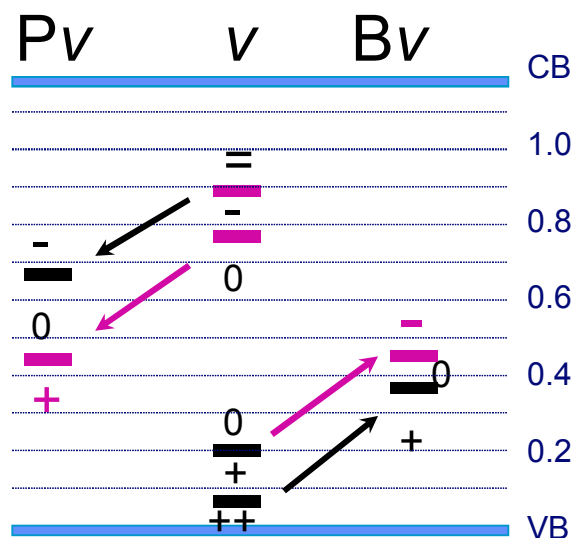
- Silicon level calculations - over 15 defects with levels

$i(= / - / 0 / + / ++)$ ,  $v(= / - / 0 / + / ++)$ ,  $vv(= / - / 0 / +)$ ,  $C_i(- / 0 / +)$ ,  $B_i(- / 0 / +)$ , **Pv**, **Bv**

$O_s$ (A-center),  $O_i$ ,  $N_s$ ,  $S_s$ ,  $v_2O$ ,  $v_2O_2$ ,  $H_i$ ,  $vP_2$ ,  $v_2P$ , ...

DFT “defect band gap” matches experiment (1.2 eV)

DFT: mean |error| = 0.10 eV, max error ~ 0.2 eV



Task: Theory quantified  $v(= / -)$ ,  $v(- / 0)$

Discovery: Theory *predicted* Pv(+) and Bv(-)

“Absolute prediction”

new levels >0.4 eV from band edge

validation error: 0.2

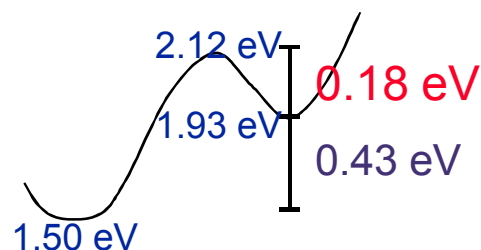
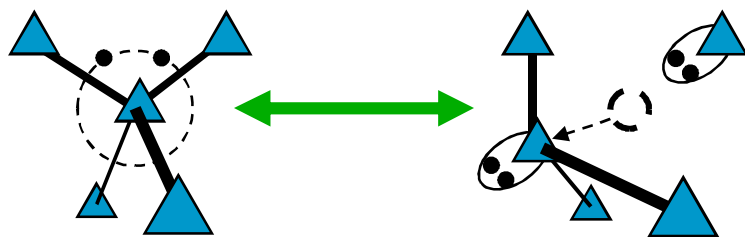
Pv(0/+) subsequently confirmed in experiment

[Larsen, et al PRL 97, 106402 (2006)]

**VALIDATION is key to quantitative DISCOVERY - GaAs is ALL discovery**

# V&V: EL2 and the As antisite

**EL2 = antisite  $\text{As}_{\text{Ga}}(0)$**



216-site =  
512-site  
(~ 64-site)

EL2(0/1+)  
EL2(1+/2+)  
Splitting:  
EL2\*  
Reorientation:

## Experiment -EL2

$E_c$  -0.74 eV  
 $E_v$  +0.54 eV  
**0.24 eV** ( $E_g=1.52$ )  
no donor states  
~0.3 eV

## SeqQuest/FDSM - $\text{As}_{\text{Ga}}$

$E_c$  -0.81 eV  
 $E_v$  +0.48 eV  
**0.25 eV**  
no donor states  
~0.2 eV

**Verification: 64-216-512-site supercell results match**

**Validation: DFT matches experiment for EL2 w/in 0.1 eV**



# The divacancy is the E1-E2 radiation center

P.A. Schultz, PRL, submitted

## Rewriting radiation physics in GaAs

Old (experimental) lore, back to 1988:

E1, E2 center =  $v_{As}(-/0)$ ,  $v_{As}(0/+)$

$E3 = v_{As} + i$

vv is dismissed

New results:

$v_{As}(-/+)$  is mid-gap negative-U (only *one* level)

$v_{As}(3-/1-)$  is upper-gap -U (*one* level)

vv(4-/3-/2-) near conduction band

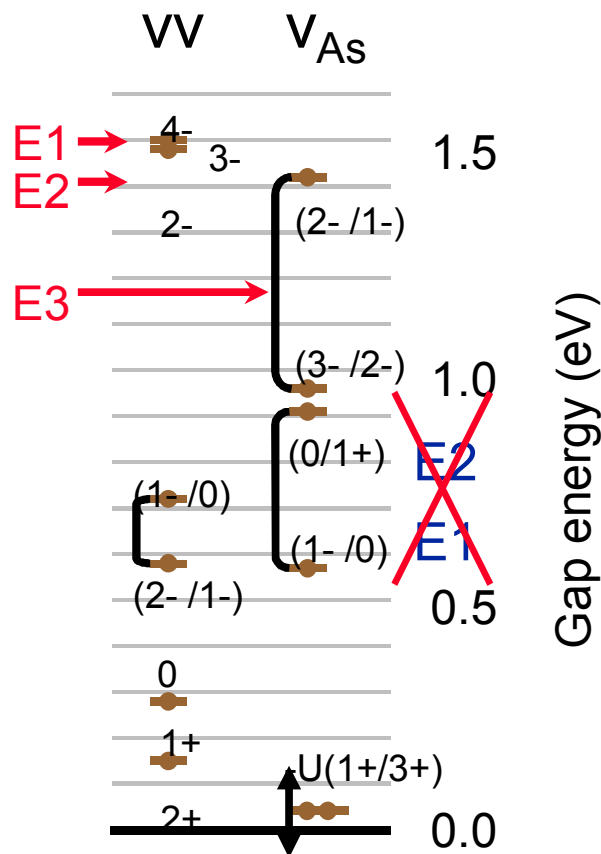
Re-analysis of expt (positron, displacement)

vv is major radiation defect: E1-E2

$vAs(3-/1-)$  transition is the E3

Differential diffusion of  $Ga_i$  and  $As_i$  is crucial element

First identified radiation defects in GaAs (EL2 was non-rad)



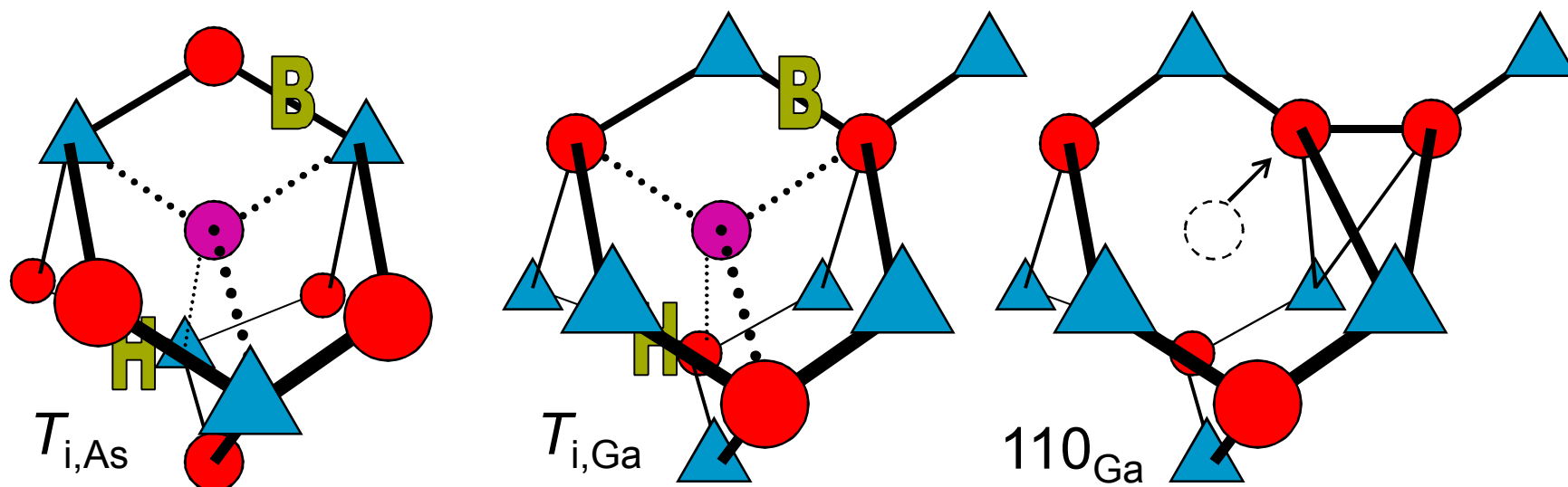
# GaAs defects: principal findings (thus far)

---

- “Simple” intrinsic defects very complicated
  - more charge states, bi/meta-stabilities, negative-U ... need theory
- Mono-vacancies have global site-shift bistability,  $v_X \leftrightarrow v_Y Y_X$ 
  - bistability must be included in unified description of vacancy
- Simple chemical motifs described bonding in ground state
  - As-pyramid (lone-pair), trivalent-Ga, weak Ga-Ga pairs across  $v$
- Interstitials have low thermal barriers for diffusion
  - $Ga_i$ : 1 eV,  $As_i$ : <0.5 V, these will be active species
- The  $As_i$  will also diffuse athermally
- The divacancy is important radiation defect (so is  $v_{As}$ )

DFT-SeqQuest/FDSM levels good enough to identify GaAs defects strictly on quantitative defect level calculations

# Ga<sub>i</sub> - gallium interstitial



Ga<sub>i</sub> only thermodynamically stable (1+) to (3+); **no stable Ga<sub>i</sub>(0)**

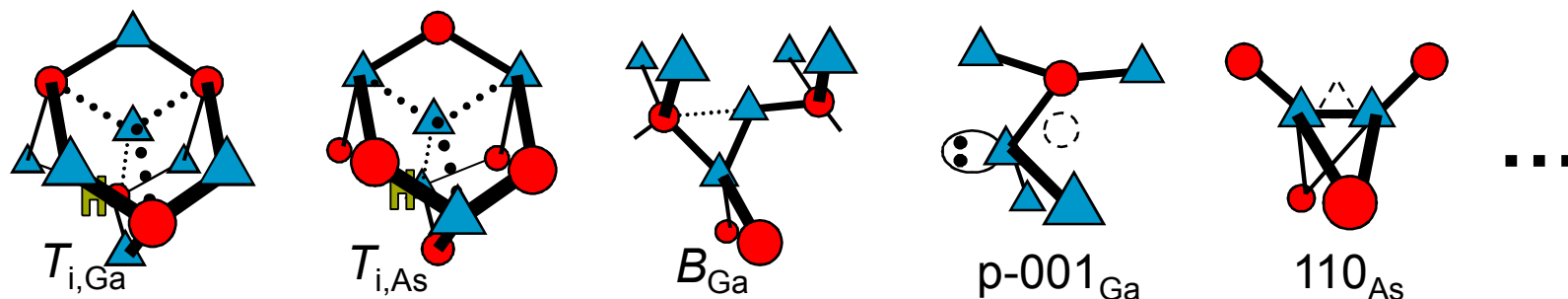
Off-network  $T_{i,Ga}$  is ground state, (1+) across full band gap

Off-network  $T_{i,As}$  is 0.27 eV higher, through 1.15(10) eV *H*-site barrier

$T_{i,As}$  takes charge states from (1+) to (3+)

Ga<sub>i</sub> electrically active (may be visible), thermally mobile (0.5-1.1 eV)

# As<sub>i</sub> - arsenic interstitial



As <sub>i</sub> (q)	ground state	next	barrier
(1-)	110 <sub>As</sub>	B <sub>Ga</sub> (+0.5 eV)	>0.5 eV
(0)	110 <sub>As</sub>	B <sub>Ga</sub> (+0.2)	>0.2 eV
(1+)	p-001 <sub>Ga</sub>	H(+0.3); B <sub>Ga</sub> (+0.4)	>0.4 eV
(2+)	H ~ B <sub>Ga</sub>	T <sub>i,Ga</sub> (+0.2); T <sub>i,As</sub> (+0.4)	~0.4 eV
(3+)	T <sub>i,Ga</sub> ~ T <sub>i,As</sub>	H(+0.4)	~0.4 eV

Charge states from (1-) to (3+)

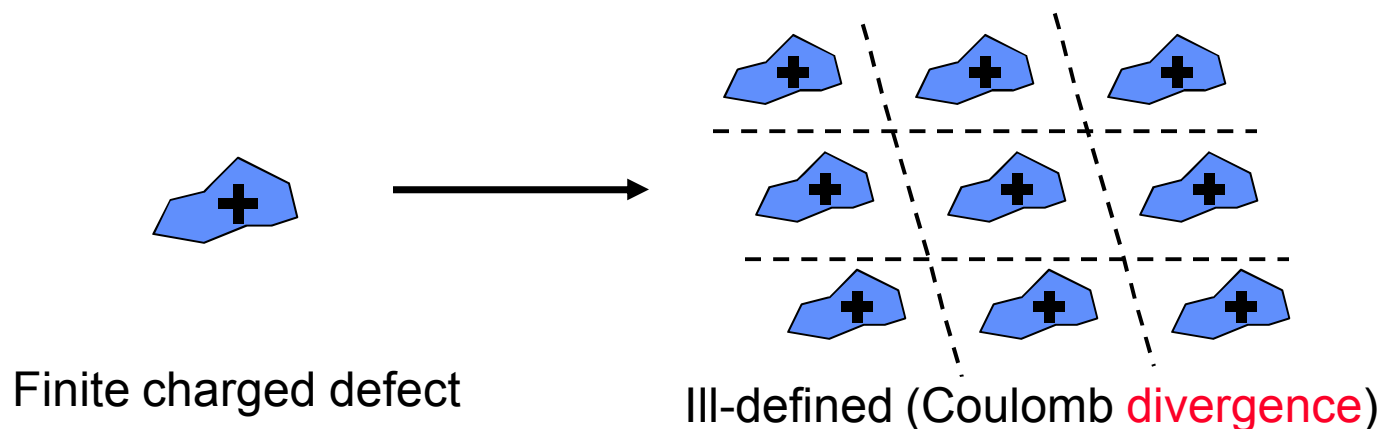
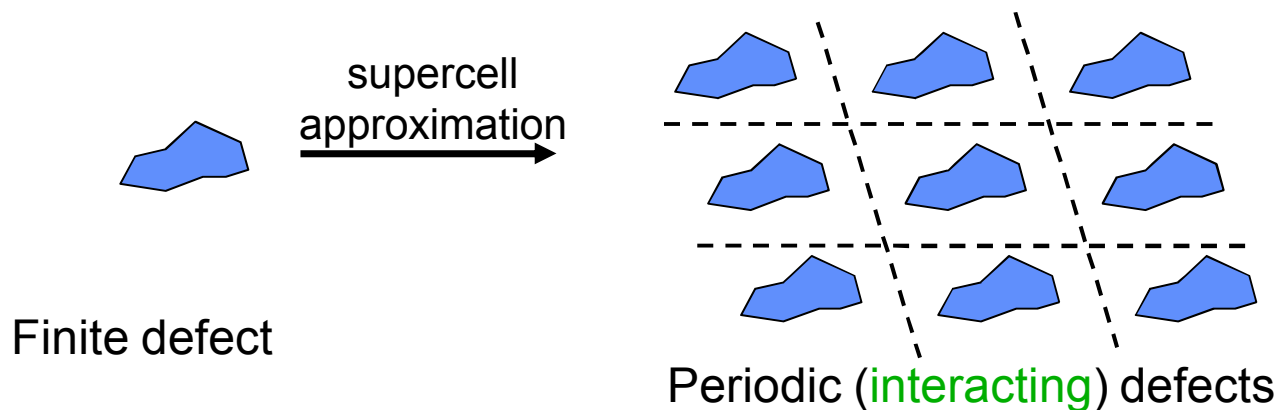
Multiply metastable, bistable from in-network(-) to off-network(+)

Low thermal barriers for diffusion: < 0.5 eV

Athermal diffusion (esp. p-type), e.g.: T(3+) - H(2+) - T(3+)

As<sub>i</sub> active, thermally mobile (<0.5 eV), athermal diffusion

# The supercell approximation



**Interactions and divergence are key issues**